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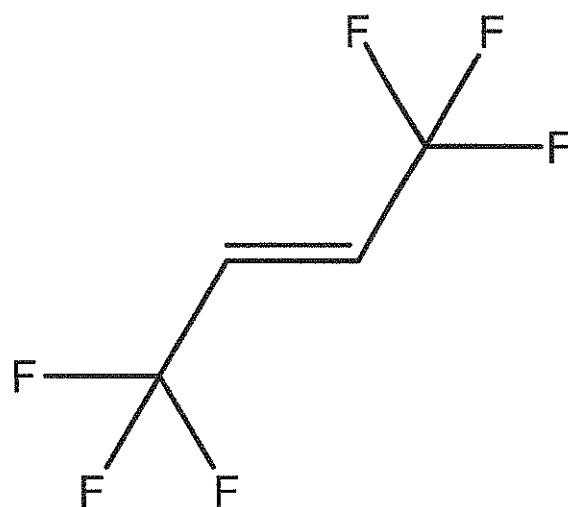


FIG 1

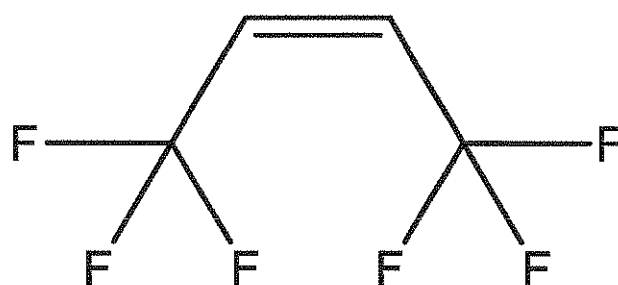


FIG 2

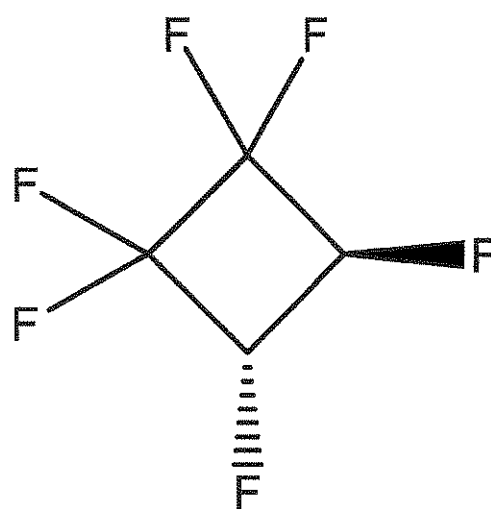


FIG 3

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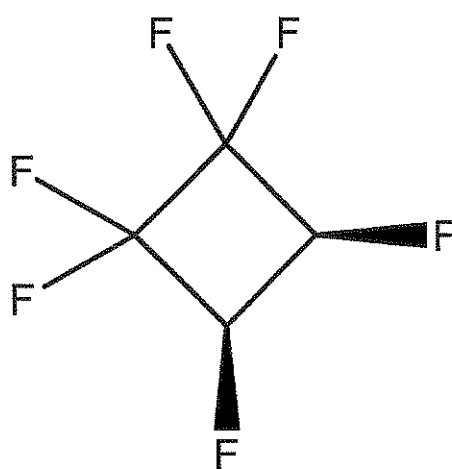


FIG 4

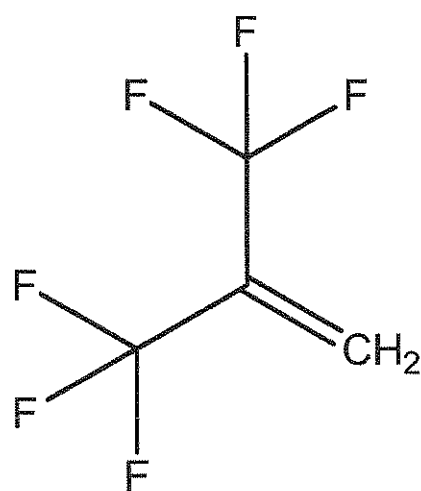


FIG 5

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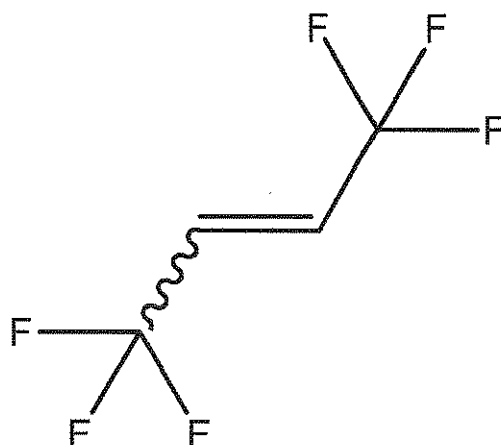


FIG 6

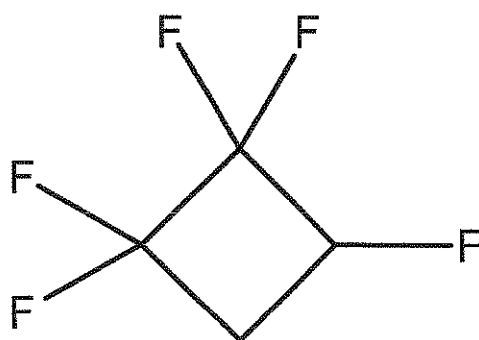


FIG 7

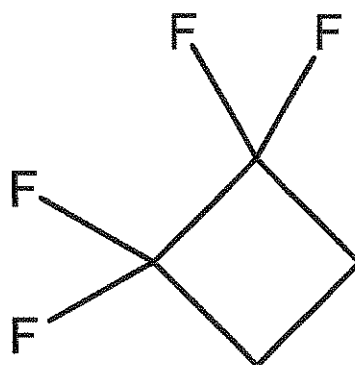
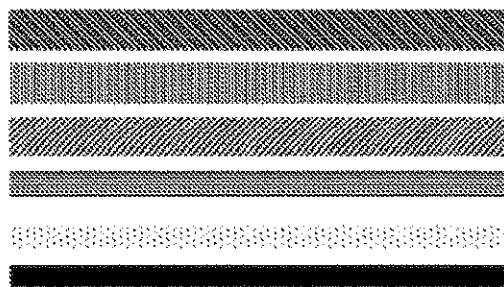
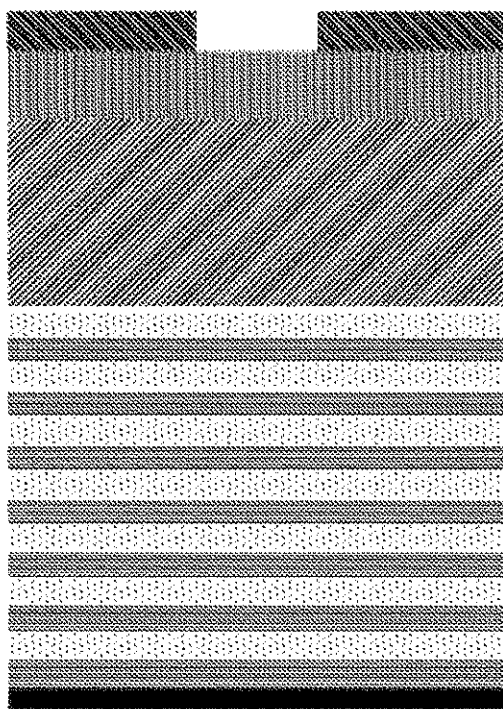


FIG 8

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photoresist  
ARC (anti reflective coating)  
APF Amorphous carbon mask  
SiN  
SiO  
Si

FIG 9

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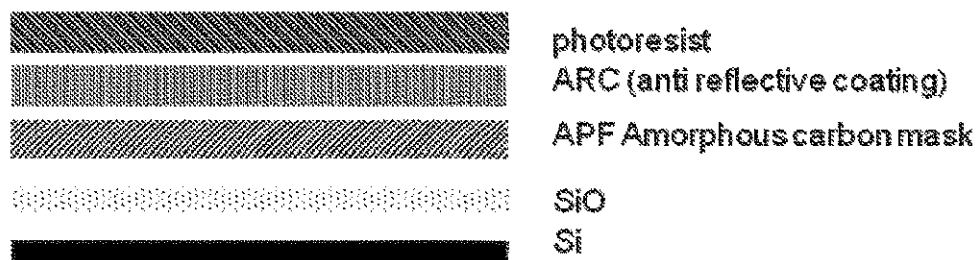
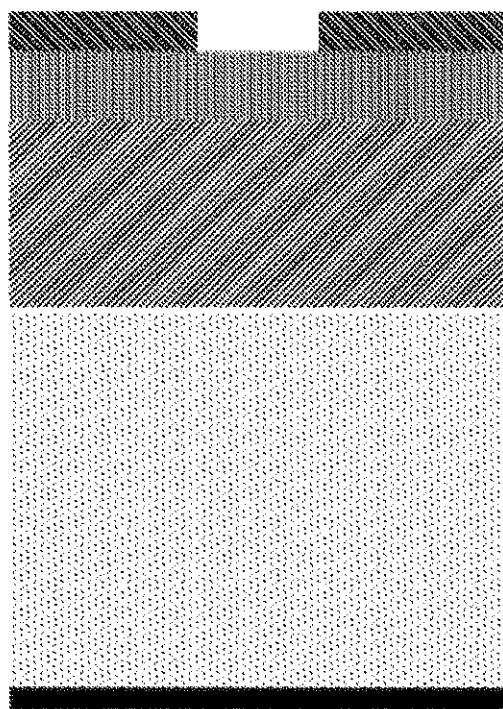


FIG 10

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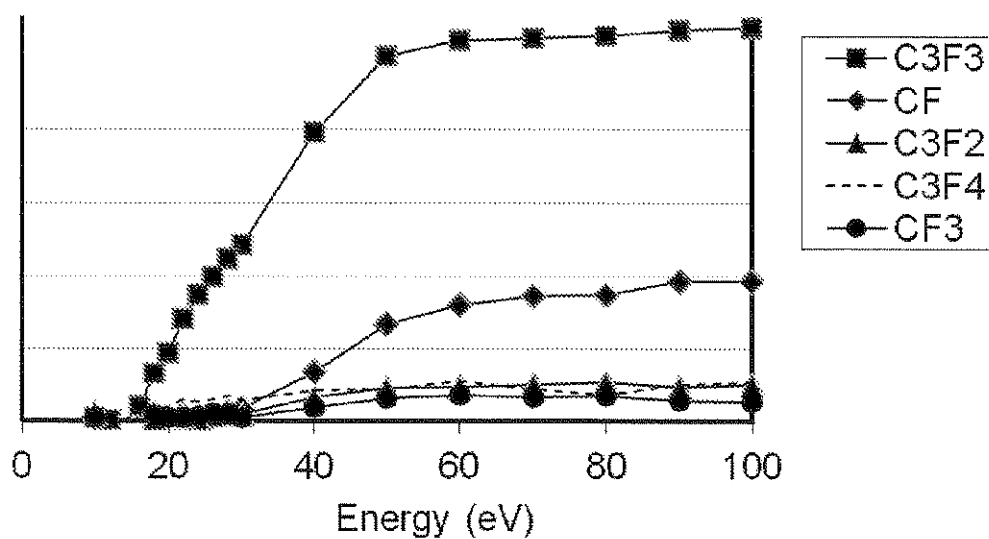
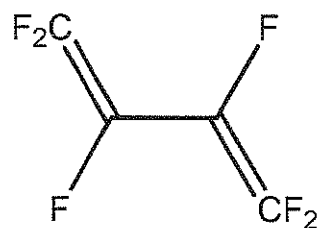


FIG 11

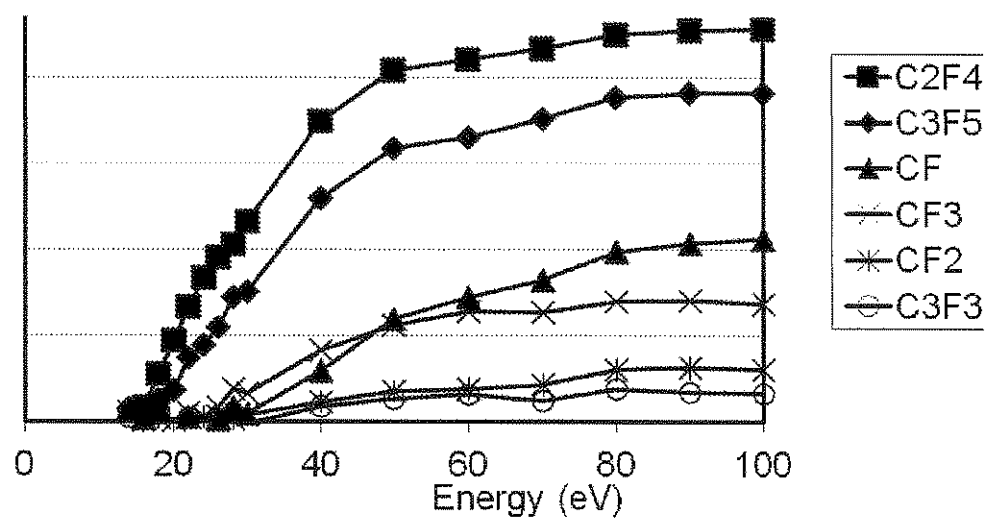
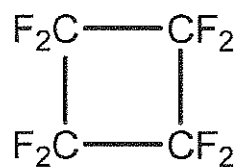


FIG 12

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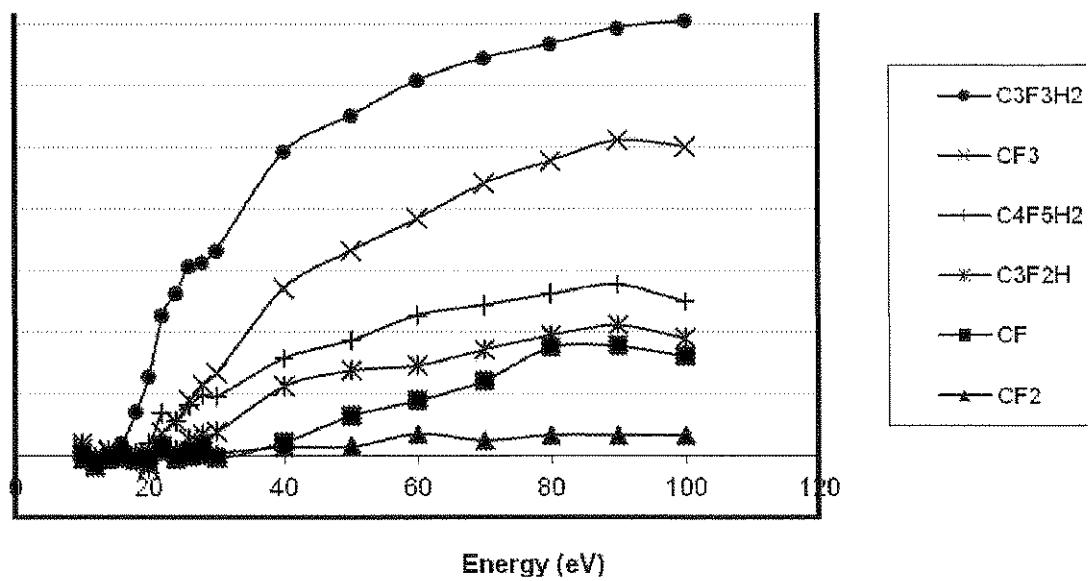


FIG 13

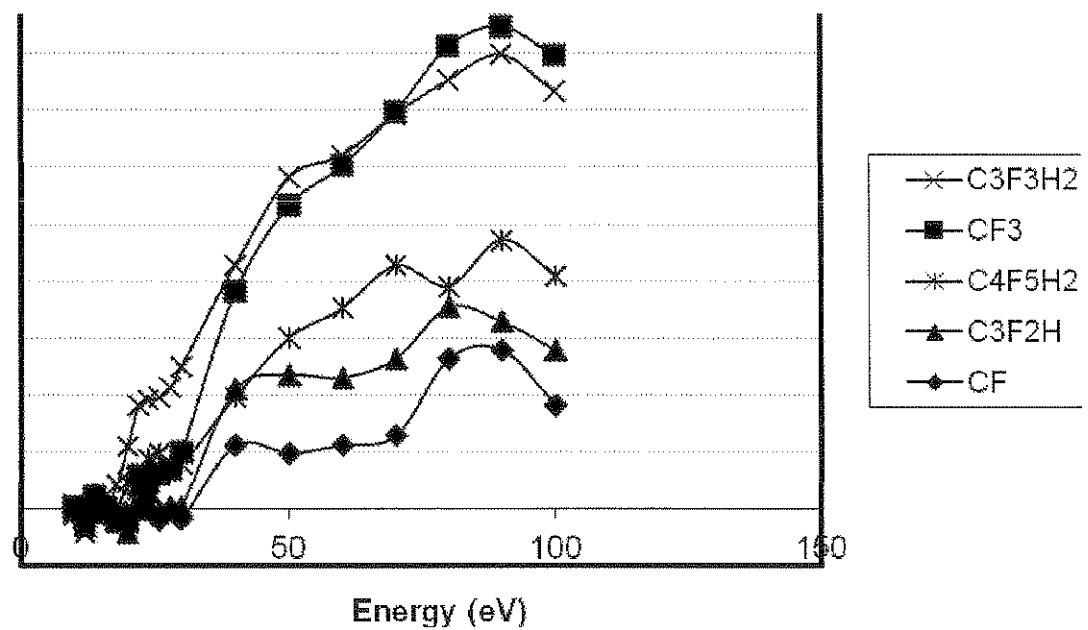


FIG 14

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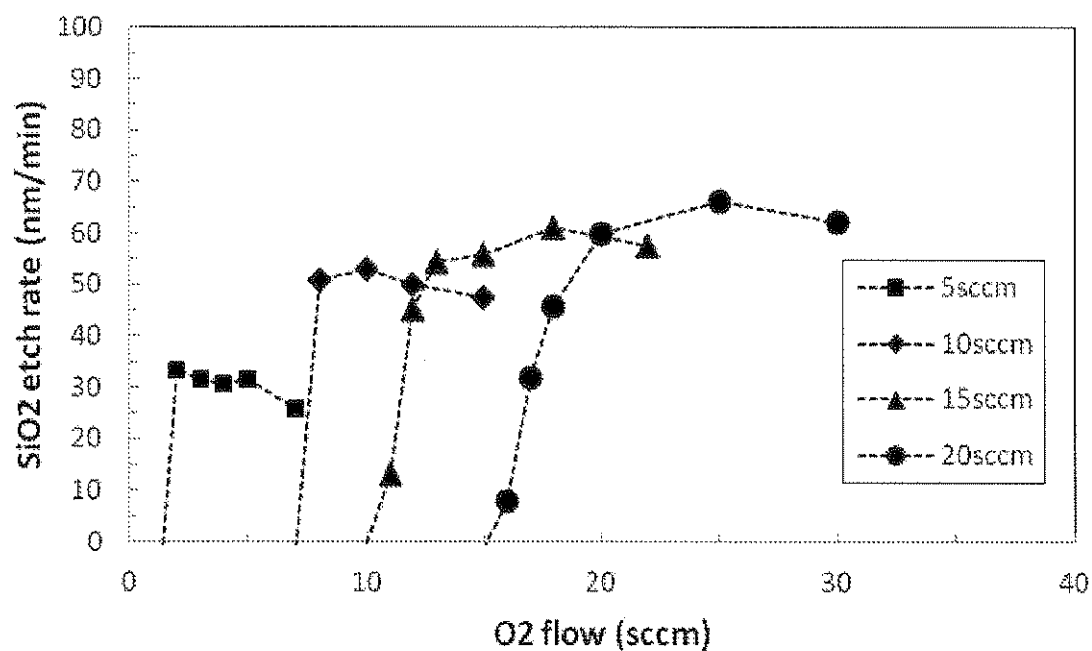
**SiO<sub>2</sub> etch rate vs O<sub>2</sub> flow**

FIG 15

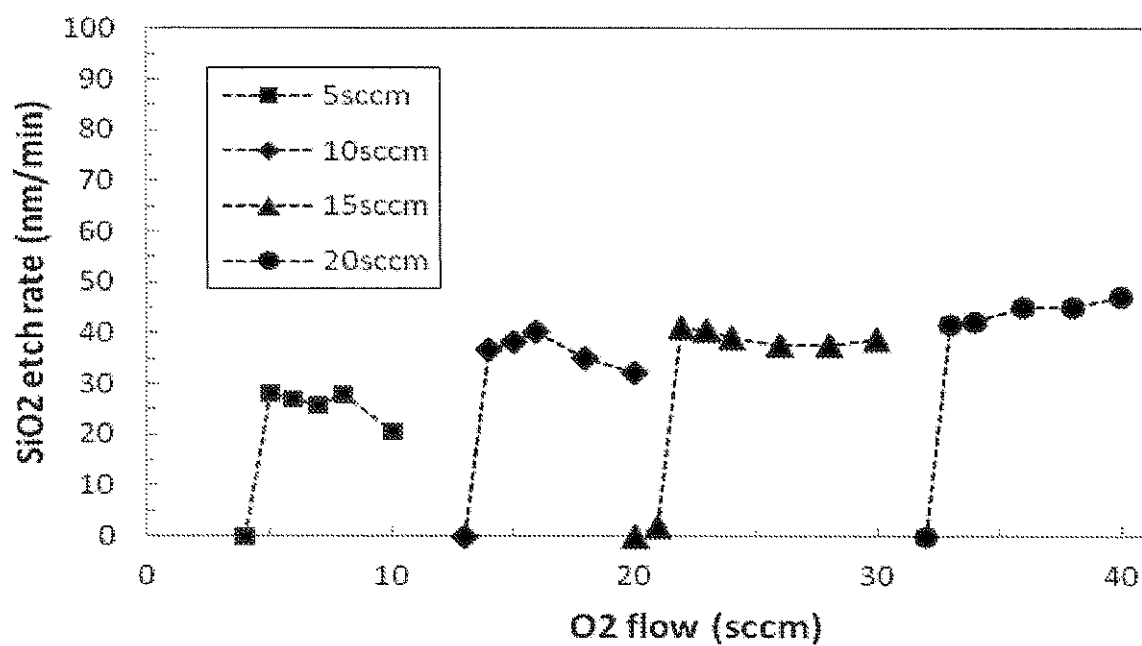
**SiO<sub>2</sub> etch rate vs O<sub>2</sub> flow**

FIG 16

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### Oxide selectivity vs O<sub>2</sub> flow

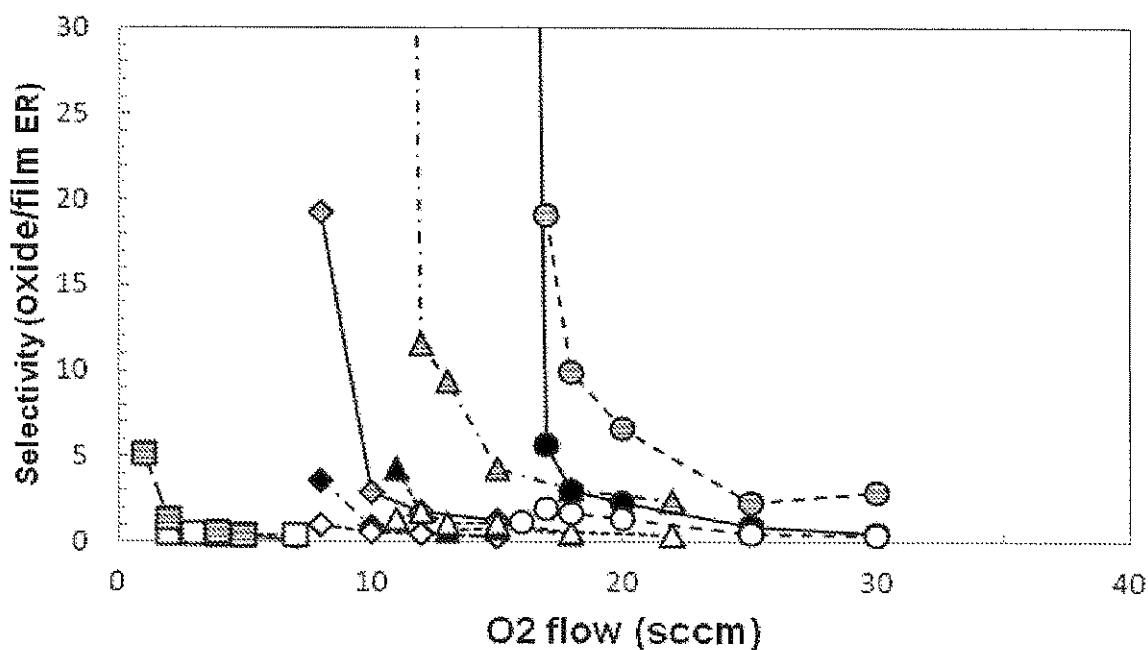


FIG 17

### Oxide selectivity vs O<sub>2</sub> flow

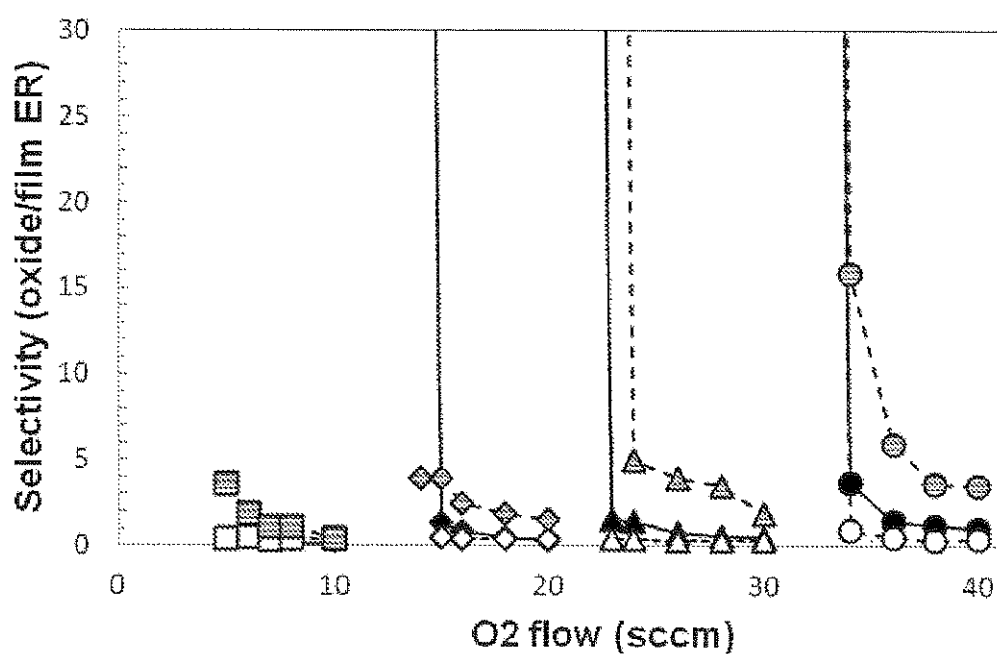


FIG 18

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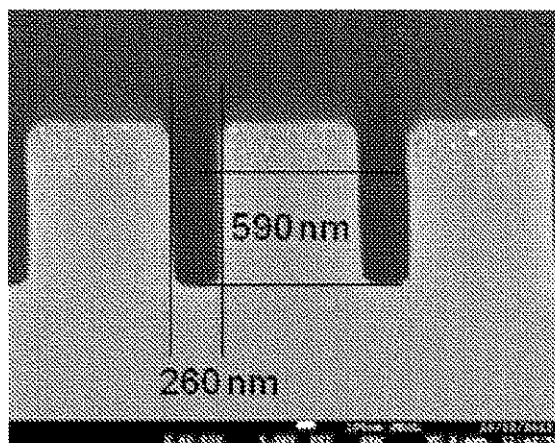


FIG 19

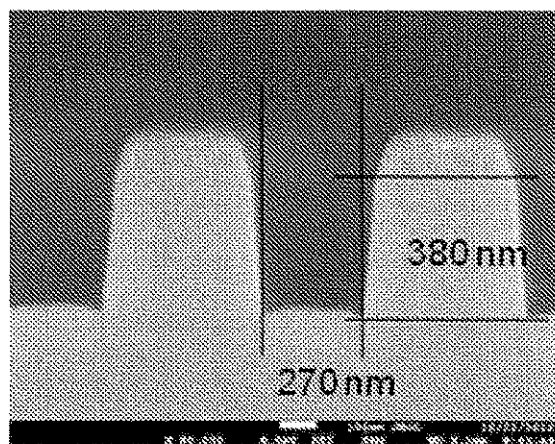


FIG 20

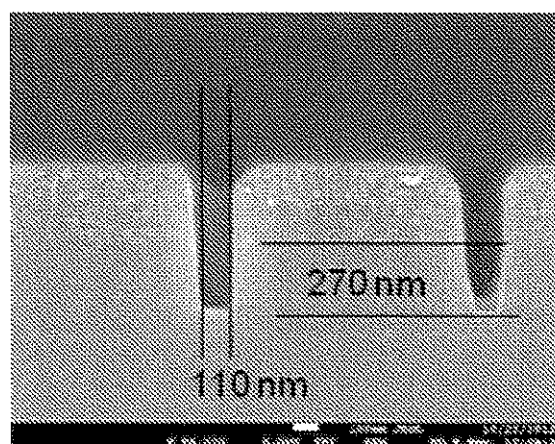


FIG 21

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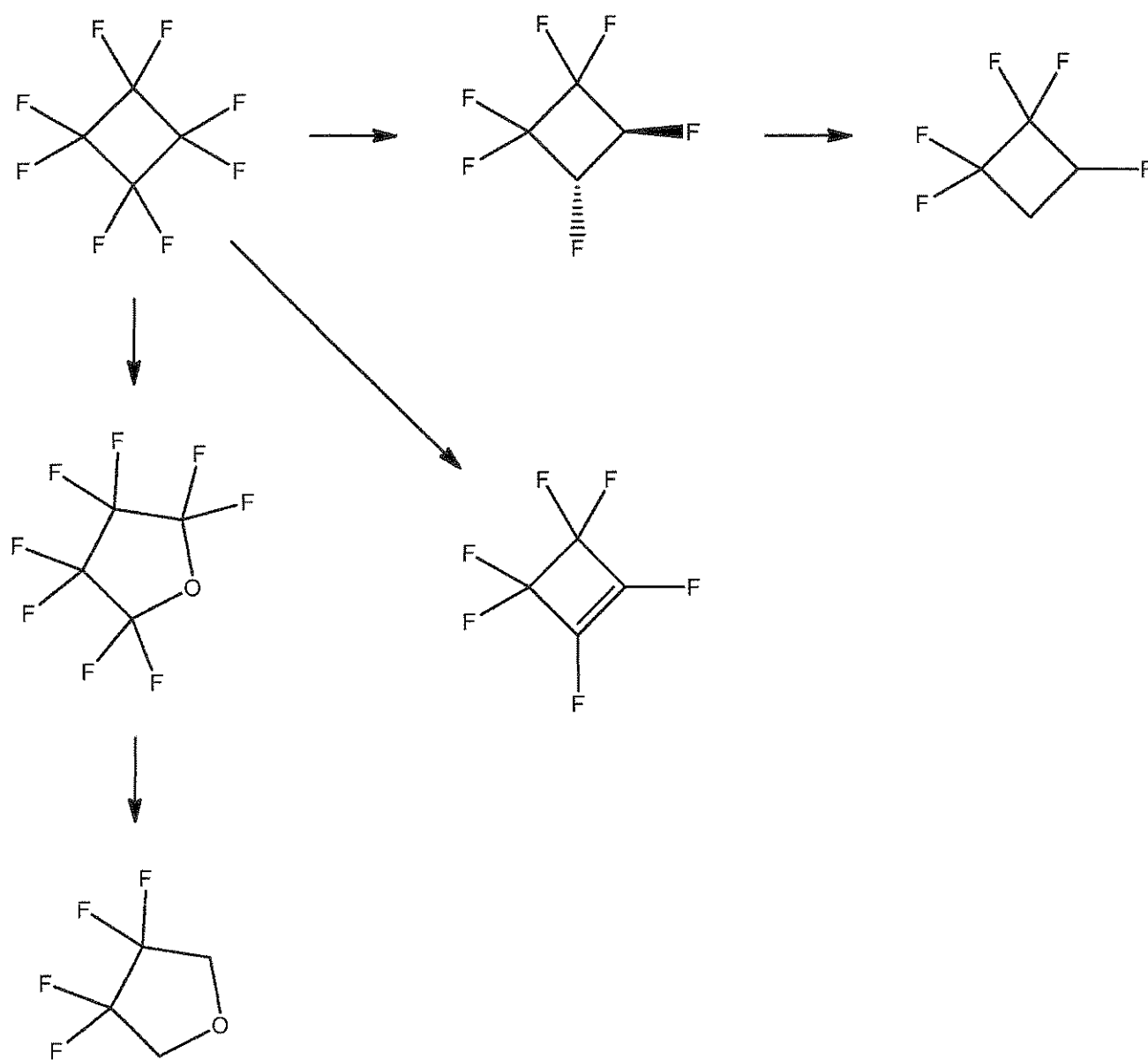


FIG 22